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(54) LIGHT-TRANSMITTING FILM AND SPUTTERING  
TARGET FOR FORMING THE SAME

SOLUTION: This sputtering target for forming light-transmitting film is composed of 0.01-10 wt% of glass-forming oxides consisting of Nb<sub>2</sub>O<sub>5</sub>, V<sub>2</sub>O<sub>5</sub>, B<sub>2</sub>O<sub>3</sub>, SiO<sub>2</sub> and P<sub>2</sub>O<sub>5</sub>, 0.01-20 wt% of Al<sub>2</sub>O<sub>3</sub>+Ga<sub>2</sub>O<sub>3</sub>, and, as necessary, 0.01-5 wt% of ZrO<sub>2</sub> and/or TiO<sub>2</sub> as rigid material oxide(s), and the rest of at least one kind of oxide selected from In<sub>2</sub>O<sub>3</sub>, SnO<sub>2</sub> and ZnO.

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a sputtering target for producing an optical disk-protective film of low reflectivity with high light transmittance through diminishing particle generation during sputtering operation, thereby reducing the frequency of suspending or stopping the sputtering operation to effect raising film production efficiency.

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